

Supporting Information for
Fabrication and Photoelectrochemical Property of Silicon/Nickel
Oxide Core/shell Nanowire Arrays

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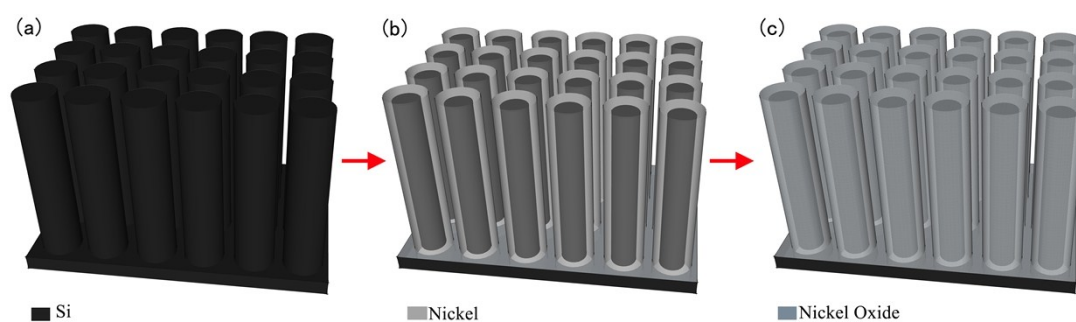


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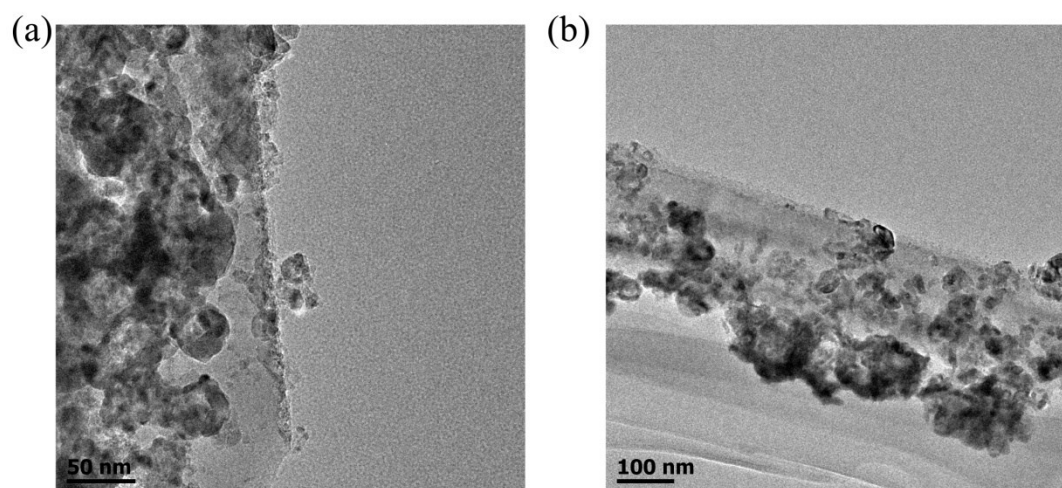


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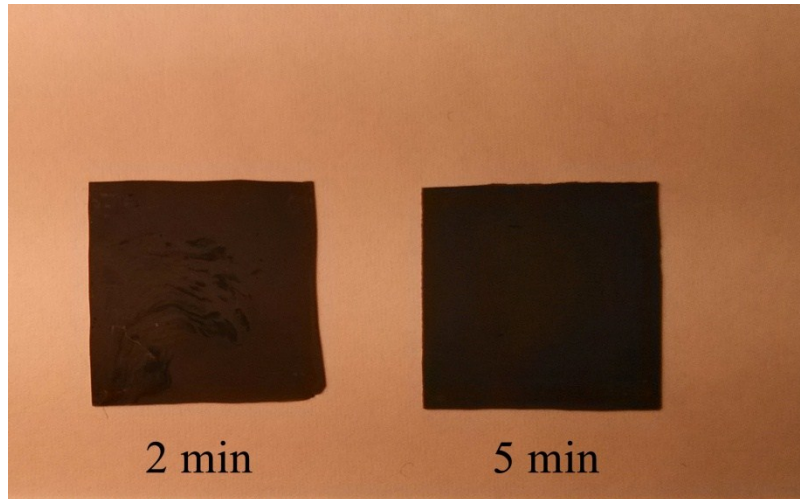


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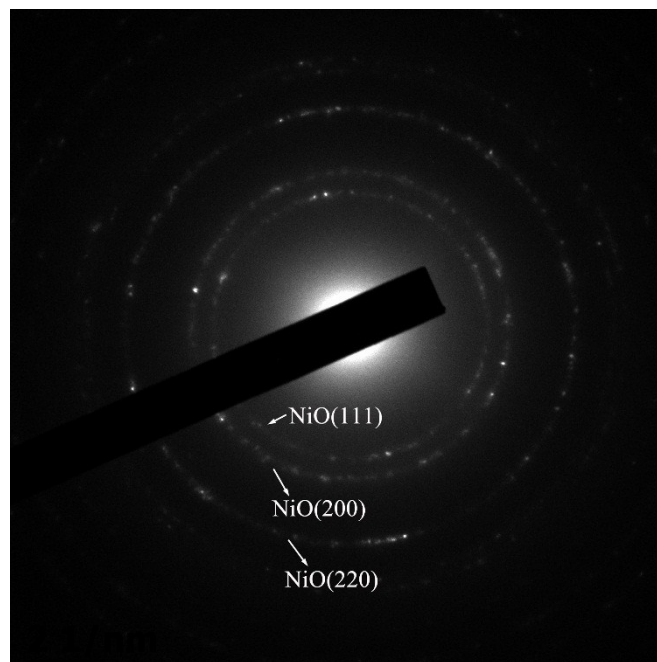


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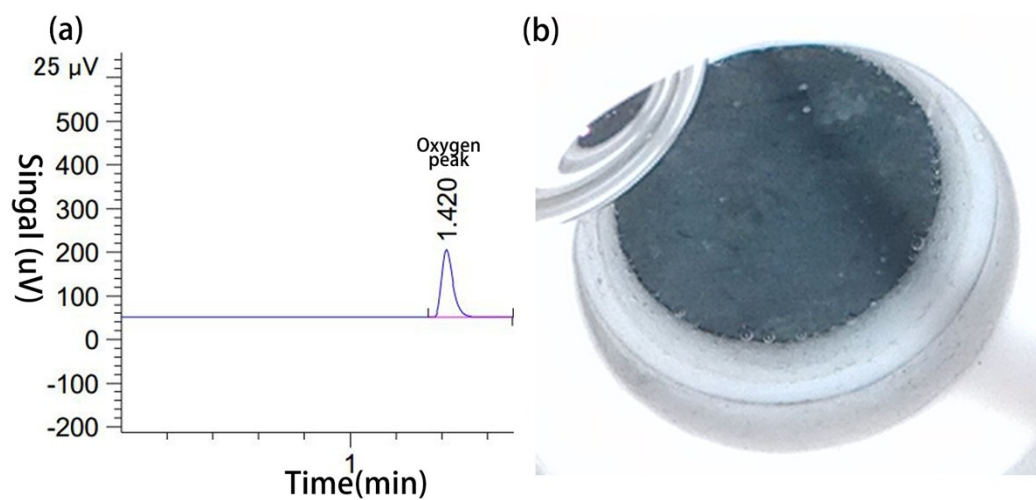


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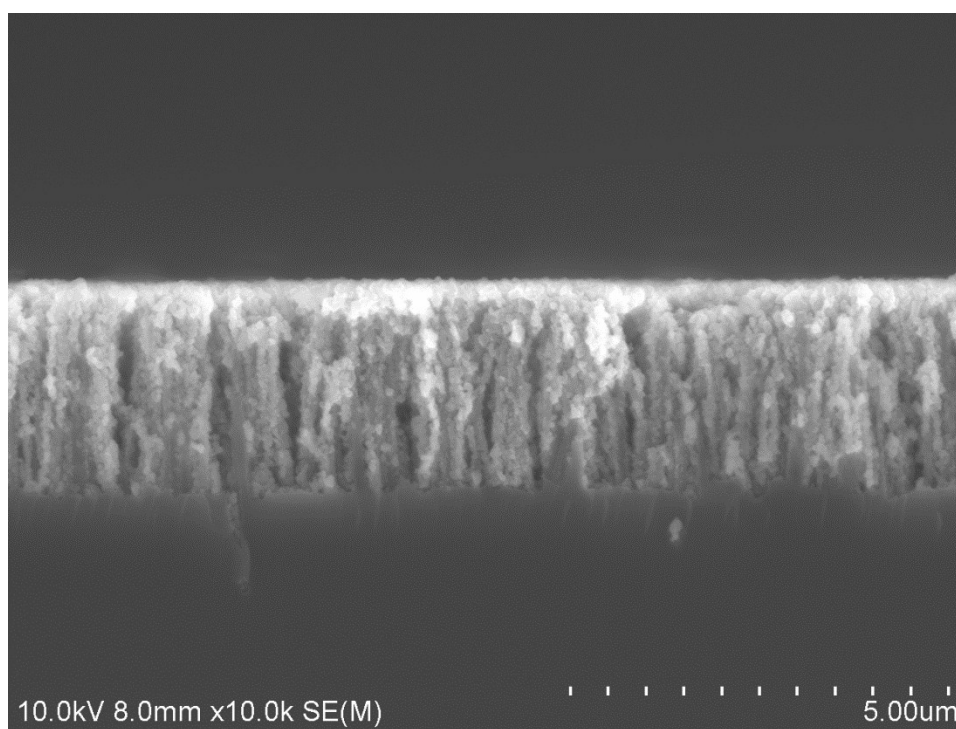


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